

ABSTRACT OF THE DISCLOSURE

A lithographic projection apparatus includes a radiation system constructed and arranged to supply a projection beam of radiation, a support structure constructed and arranged to support a patterning structure, the patterning structure constructed and arranged to pattern the projection beam according to a desired pattern, a substrate support constructed and arranged to support a substrate, and a projection system constructed and arranged to project the patterned beam onto a target portion of the substrate. The apparatus further includes a gas flushing system comprising radial gas flow outlets, said gas flushing system being constructed and arranged to generate a radial gas flow through said radial gas flow outlets in an intermediate space defined between said gas flushing system and said substrate, wherein the radial gas flow has a radial velocity directed outwards in said space with a magnitude larger than zero at every location in said space.